

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (Currently Amended) An ion-implantation machine, comprising:
an implantation chamber having a vent inlet;
a vacuum pump connected to said implantation chamber; and
means for connecting said vent inlet to a source of a fluid containing oxygen
decontaminating the implantation chamber by supplying air into the implantation
chamber through the vent inlet.
2. (Canceled)
3. (Currently Amended) The ion-implantation machine according to claim 2
1 wherein said means for connecting-supplying comprise a pipe, which has an open inlet that is
open to the air and an outlet connected to said vent inlet.
4. (Original) The ion-implantation machine according to claim 3 wherein
said pipe comprises flow-rate control means.
5. (Currently Amended) ~~The ion-implantation machine according to claim 4,~~
~~further comprising~~
An ion-implantation machine, comprising:
an implantation chamber having a vent inlet;
a vacuum pump connected to said implantation chamber;
means for connecting said vent inlet to a source of a fluid containing oxygen,
wherein said fluid containing oxygen is environmental air, and wherein said means for

connecting comprise a pipe having an open inlet, an outlet connected to said vent inlet, and flow-rate control means; and

a protection valve arranged between said vacuum pump and said implantation chamber, and a control unit, controlling said protection valve, wherein said flow-rate control means comprise a vent valve controlled by said control unit.

6. (Original) The ion-implantation machine according to claim 5 wherein said pipe further comprises a flow-rate measuring valve.

7. (Original) The ion-implantation machine according to claim 5 wherein said pipe further comprises a particulate filter.

8. (Currently Amended) The ion-implantation machine according to claim 6 5 wherein said control unit comprises means for inhibiting said vent valve when the protection valve is open.

9. (Original) The ion-implantation machine according to claim 8 wherein said control unit comprises: an electronic control module, including a control inlet, a first valve driving branch controlling said protection valve, and an auxiliary driving branch controlling said vent valve; and a switching module, having an inlet connected to said control inlet, a first outlet connected to said first valve driving branch, and a second outlet connected to said auxiliary driving branch.

10. – 20. (Canceled)

21. (Currently Amended) An ion-implantation machine, comprising:
an implantation chamber;
a vacuum pump;
an oxygen source;

a first valve positioned between the vacuum pump and the implantation chamber;
a second valve positioned between the oxygen source and the implantation chamber; and

a controller coupled to the first and second valves and structured to alternately open the first valve to create a vacuum in the implantation chamber during a dopant implant phase and open the second valve to provide oxygen to the implantation chamber during a decontamination phase, wherein said controller comprises:

an electronic control module that includes a control line, a first valve driving branch controlling said first valve, and second driving branch controlling said second valve; and

a switching module having an input connected to said control line, a first output connected to control said first valve driving branch, and a second output connected to control said second driving branch.

22. (Original) The ion-implantation machine according to claim 21 wherein oxygen source includes an input port connected to environmental air.

23. (Original) The ion-implantation machine according to claim 21 wherein said controller comprises means for inhibiting said first valve when the second valve is open.

24. (Canceled)

25. (Currently Amended) An ion-implantation machine, comprising:
means for implanting heavy ionic species in a wafer positioned in an implantation chamber kept in vacuum conditions; and

decontaminating means for decontaminating said implantation chamber by supplying a fluid containing oxygen into the implantation chamber, wherein said implantation chamber includes a vent inlet and said decontaminating means include a vent pipe having a flow-

rate metering valve connected to said vent inlet, wherein said vent pipe further comprises a particulate filter.

26. (Previously Presented) The ion-implantation machine according to claim 25, further comprising:

a cryogenic pump connected to the implantation chamber; and

control means for enabling the cryogenic pump to vacuum the implantation chamber while the heavy ionic species are implanted in the wafer and for disconnection the cryogenic pump from said implantation chamber when the implantation chamber is decontaminated.

27. (Previously Presented) The ion-implantation machine according to claim 25 wherein said decontaminating means comprise means for supplying environmental air to said implantation chamber.

28. -29. (Canceled) .

30. (Currently Amended) The ion-implantation machine according to claim 25 wherein said ~~heaving~~heavy ionic species are first ionic species and said decontaminating means include means for decontaminating the implantation chamber during crossover between said heavy ionic species and second ionic species lighter than said heavy ionic species.

31. (Canceled)

32. (Currently Amended) ~~The ion-implantation machine according to claim 25~~
An ion-implantation machine, comprising:

means for implanting heavy ionic species in a wafer positioned in an implantation chamber kept in vacuum conditions; and

decontaminating means for decontaminating said implantation chamber by supplying a fluid containing oxygen into the implantation chamber, wherein said decontamination means includes:

a pipe having an open inlet exposed to air, an outlet connected to said vent inlet, and a vent valve that controllably supplies air from the open inlet to the vent inlet via the outlet of the pipe; and

a control unit having a first control branch that controls the vent valve to supply air to the implantation chamber for decontamination of the implantation chamber.

33. (Previously Presented) The ion-implantation machine according to claim 32, further comprising:

a vacuum pump; and

a vacuum valve connected between the vacuum pump and the implantation chamber wherein said control unit includes a second control branch connected to the vacuum valve and structured to open the vacuum valve to enable the vacuum pump to vacuum the implantation chamber during the implantation of the heavy ionic species.

34. (New) The ion-implantation machine according to claim 32 wherein the control unit is structured to control the vent valve to supply air to the implantation chamber at a pressure that maintains a pressure within the implantation chamber between 1×10^{-5} and 5×10^{-5} torr.

35. (New) The ion-implantation machine according to claim 1 wherein the means for decontaminating the implantation chamber includes means for maintaining a pressure within the implantation chamber between 1×10^{-5} and 5×10^{-5} torr.